Power Gan FETs Performance, efficiency, reliability





Innovation opens up new Efficiency Wins opportunities

Innovation is in many ways synonymous with the Semiconductor industry. Take a small step back and you quickly see how the industry has driven significant change in all our lives. Consumer and industry requirements continue to evolve and the focus for innovation has clearly swung around to efficiency.

One area where demand for improved device efficiency is set to grow significantly in the next few years is high-power FETs. Just look at the power requirements for hybrid and electric vehicles or even the mounting pressure on large scale IoT infrastructure.

Getting the right power density while ensuring the best repetitive Safe Operating Area (SOA) and delivering both device and thermal efficiency, requires a specific mix of capabilities and expertise. When it comes to low and medium power MOSFETs, Nexperia fully understands this challenge. By adding Gallium Nitride (GaN) technology to our portfolio, this means we can also address this challenge in the high-power FET arena.

Nexperia has been developing and investing in our GaN capabilities for a number of years. This gradual build up has given us the time to understand the technology and where and how it can be best utilized going forward. That ensures we can meet the quality demands critical to the automotive industry and continue to deliver Efficiency Wins in the long-term.

Frans Scheper

CEO Nexperia

Building on proven processes

From product concept and design to manufacturing and sales, getting the smallest details right helps the world's most demanding industries make quality and efficiency gains. Key to Nexperia's success has been a strong commitment to meet and even go beyond the stringent quality standards our customers demand, and this standard level also applies to our development of power GaN FETs.

Whether that is internationally recognized standards for quality (ISO 9000), the environment (ISO 14001), health and safety (ISO 45001 / OHSAS 18001) or industry specific (IATF 16949), all our customers benefit from products that are built on proven zero defect, six-sigma and safe-launch processes. Owning our own industrial front-end and assembly infrastructure ensures we can control every aspect, so you can expect the same level of service and response as you already experience across the Nexperia portfolio to be applied to our GaN FET offering.

Any new technology requires an increased level of confidence, this is why we also do application and technology specific quality and reliability testing within the development of all GaN FETs.

Automotive grade

As an established supplier into the automotive industry our rigorous attention to detail and commitment to automotive quality yields sub-part-per-million (sub-ppm) failure rates across our existing portfolio of Discretes, Logic and MOSFETs. We extend our AEC-Q101 qualification into our GaN FETs development.

GaN-on-Si: Power and efficiency in one package

Power conversion efficiency is a key growth driver in electronics but there is often a trade-off between density and efficiency.

When it comes to getting very high efficiency and high-power density, then 650 V GaN-on-Si FETs offer an ideal solution. These devices allow high frequency operation with high breakdown voltages and high current carrying capabilities. A substantially lower switching figure of merit ($R_{DS(on)} \times Q_{GD}$) and reverse recovery charge (Q_{rr}), enable the high switching frequencies while delivering lower dissipation and more efficient power conversion.

Features and benefits

- > Ultra low reverse recovery loss
- Easy simple gate drive (0 V to +10 V or 12 V), easy to drive
- > Robust gate oxide quality (+ 20 V capability)
- High gate threshold voltage (+4 V) for very good gate bounce immunity
- Integrated very low Vf body diode.
 No external antiparallel diode required.
- Bidirectional topology. Reverse conduction capability
- > Easy to control slew rate for turn on and turn off
- Large transient voltage capability (800 V for 650 V devices)

Low reverse recovery loss compared to silicon devices, same test circuit



GaN-on-Si: the process game changer

Compound or III-V semiconductors, such as GaN, often offer performance benefits compared to Silicon (Si). For example GaN is mechanically stable, has a wide bandgap with high heat capacity and comparable thermal conductivity. However, III-V semiconductors tend to be more costly to process. Growing thick GaN epitaxial layers on large diameter Si substrate is a recent breakthrough. It reduces costs per wafer to a competitive level for power applications and allows processing in existing 200 mm fabs.

Where performance

Efficient power use is a key industrial challenge and a driver for innovation. Societal pressure and legislation are demanding increasing efficiencies in power conversion and control. For some applications power conversion efficiency and power density are critical for market adoption. Prime examples include the trend towards automotive electrification and the high-voltage communications and industrial infrastructure sectors. GaN FETs enable smaller, faster, cooler, lighter systems, with lower overall system cost.

Powering the IoT infrastructure

ounts

Providing us with the always on cloud connectivity, processing power and storage we demand takes a lot of power. Very efficient high-end power supplies are needed to deliver the reduced power losses in **industrial automation, data centres,** and **telecommunications infrastructure.** That is why the improved density and efficient power conversion offered by GaN-on-Si is critical.

Electrification of the powertrain

With every gram of CO₂ exhaust being vital in today's cars, it is driving the move to vehicle electrification. From hybrids through to full electric vehicles, electrification of the powertrain is expected to dominate power semiconductor market growth in the next two decades. The power density and efficiency of GaN-on-Si will play a leading role in this space, specifically for **on-board-chargers** (EV charging), DC/DC converters and motor drive traction inverters (xEV traction inverters).



Solutions

Power GaN FETs demonstrate superior performance in various solutions:

- > Hard switching for AC-DC Totem pole PFC applications
- > LLC phase shift full-bridge (resonant or fixed frequency) for soft-switching applications
- > All DC-AC inverter topologies
- > AC-AC matrix converters using bidirectional switches



GaN FET half-bridge

GaN FET half-bridge

Power GaN FETs with their ultra-low Q_{rr} and very fast switching transitions can reduce switching losses to offer the highest efficiencies. Switching applications can benefit from GaN FETs, and whether AC-DC, DC-DC or DC-AC multi-phase inverters, the half-bridge configuration is an integral part of these solutions.



GaN FET Totem Pole PFC

Power GaN FETS out perform all other devices in hard-switching applications using totem pole topologies to improve performance whilst reducing component count by 50 %. Lower component count reduces cost, improves power density, whilst increasing overall system reliability. Improved overall system power efficiency has the secondary effect of reducing the requirement for expensive cooling systems and the related operating costs in closed environments.





V₀

 C_2

GND



Totem Pole PFC

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Products

Nexperia's current GAN FET products and development roadmap are focussed on delivering reliable products to support both automotive and IoT infrastructure applications. Our GaN process technology is based on our robust and proven production processes which now generates industry leading power GaN FETs.

Features and benefits:

- > Easy gate drive, low R_{DS(on)}, fast switching
- > Excellent body diode (Low Vf), low Q
- > High ruggedness
- > Low dynamic R_{DS(on)}
- > Stable switching
- > Rugged gate bounce immunity (Vth ~ 4 V)

GAN063-650WSA – Power GaN FET 650V			GAN041-650WSA – Power GaN FET 650 V			
xC	V _{DS}	650 V		xC	V _{DS}	650 V
	V _{TDS}	800 V			V _{TDS}	800 V
	R _{DS(on)} max	60 mΩ			R _{DS(on)} max	41 mΩ
	R _{DS(on)} typ	50 mΩ			R _{DS(on)} typ	35 mΩ
	Package	TO-247 (SOT429)			Package	TO-247 (SOT429)
	E _{oss}	15 µJ @ 400 V			E _{oss}	22 µJ @ 400 V
	Q _{rr}	125 nC @ 400 V -1000 A/µS			Q _{rr}	178 nC @ 400 V -1000 A

Developing for the future:

We remain focussed on the development of very high reliability-high quality power GaN FETs, with continued development in:

- Automotive qualification
- 900 V and upwards
- Half-bridge package solutions
- LFPAK clip-bond packaging
- Bare die





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Date of release: February 2019

Printed: In the Netherlands

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